



Intermolecular to Present Results at ALD 2016 from its High-Throughput Experimentation Platform and State-of-the-Art ALD Technology

- **Includes investigation of Nickel and Nickel Nitride as high work function electrode layers**
- **Shows non-contact, site-addressable ALD for rapid development of advanced thin film stacks**
- **Utilized Intermolecular's combinatorial ALD hardware to study H₂O₂ as alternate oxidant for metal oxide deposition**

SAN JOSE, Calif. – July 25, 2016 – [Intermolecular, Inc.](#) (NASDAQ: IMI), the trusted partner in materials innovation, today announced it will present at [ALD 2016](#) on Wednesday, July 27, 2016, in Dublin, Ireland. Nobi Fuchigami, Member of Technical Staff at Intermolecular, will review atomic layer deposition (ALD) processes for thin (<5nm) nickel and nickel nitride films using amidinate precursors for high work function electrode layers. The experiments were performed using Intermolecular's high-throughput experimentation platform and state-of-the art ALD site-isolated and quad combi ALD reactor technology.

In addition, Karl Littau, Ph.D, Senior Principal Scientist at Intermolecular, will present two posters showcasing the following:

- Intermolecular's ALD technology demonstrating non-contact, site addressable ALD reactions across a 300mm wafer in an ALD chamber integrated on a cluster tool.
- The comparison between RASIRC BRUTE™ hydrogen peroxide (H₂O₂) and ozone (O₃) as the oxidant for zirconium oxide (ZrOx) utilizing Intermolecular Combinatorial ALD hardware.

About Intermolecular, Inc.

Intermolecular® is the trusted partner for advanced materials innovation. Advanced materials are at the core of innovation in the 21st century for a wide range of industries including semiconductors, consumer electronics, automotive and aerospace. With its substantial materials expertise; accelerated learning and experimentation platform; and information and analytics infrastructure, Intermolecular has a ten-year track record helping leading companies accelerate and de-risk materials innovation.

“Intermolecular” and the Intermolecular logo are registered trademarks; all rights reserved. Learn more at www.intermolecular.com or follow on Twitter at @IMIMaterials.

Contacts

PRESS CONTACT:

Kelly Karr

Tanis Communications, Inc.

kelly.karr@taniscomm.com

+408-718-9350

3011 North First Street, San Jose, CA 95134 (408) 582-5700 / (408) 582-5401 fax